

ENGINEERING TRIPOS PART IIB

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Friday 2 May 2008 9 to 10.30

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Module 4B6

SOLID STATE DEVICES AND CHEMICAL/BIOLOGICAL SENSORS

*Answer not more than **three** questions*

*All questions carry the same number of marks.*

*The **approximate** percentage of marks allocated to each part of a question is indicated in the right margin.*

*There are no attachments.*

STATIONERY REQUIREMENTS

Single-sided script paper

SPECIAL REQUIREMENTS

Engineering Data Book

CUED approved calculator allowed

Supplementary pages: None

**You may not start to read the questions printed on the subsequent pages of this question paper until instructed that you may do so by the Invigilator**

1 (a) Explain the meaning of deep depletion in an MOS capacitor. [20%]

(b) Calculate the voltage applied to an ideal p-type silicon MOS capacitor in deep depletion, for the following parameters:

|                                   |                                |       |
|-----------------------------------|--------------------------------|-------|
| oxide thickness                   | $d = 10^{-7} \text{ m}$        |       |
| oxide dielectric constant         | $\epsilon_i = 3.9\epsilon_0$   |       |
| semiconductor dielectric constant | $\epsilon_s = 11.9\epsilon_0$  |       |
| acceptor concentration            | $N_A = 10^{21} \text{ m}^{-3}$ |       |
| surface potential                 | $\psi_s = 4\text{V}$           | [30%] |

(c) Explain what is meant by linear and saturation regimes in a MOSFET.

Sketch the conductance as a function of position in the channel and identify the pinch-off region, when present:

(i) in the linear regime;

(ii) for  $V_{DS} = V_{Dsat}$ ;

(iii) for  $V_{DS} > V_{Dsat}$  [30%]

(d) What is the value of the channel potential at the left hand boundary of the pinch-off region? [20%]

Note:

The fixed charge per unit area in the depletion region, where symbols have their standard meaning is given by

$$Q_B = - [2 \epsilon_s q N_A \psi_s]^{\frac{1}{2}}$$

2 (a) Explain how the double layer originates at a metal-electrolyte and at an insulator-electrolyte interface. Discuss why the double layer potential is important for biosensor applications. Give examples. [50%]

(b) A water-based electrolyte, in contact with a planar electrode, contains positive and negative ions in equal concentrations,  $n^+ = n^- = n_0 = 10^{24} \text{ ion m}^{-3}$ . Each ion carries a charge equal in magnitude to  $q = 1.6 \times 10^{-19} \text{ Coulomb}$ .

Prove that Poisson's Equation for this system can be written in the following form:

$$\frac{d^2\psi}{dx^2} = -\frac{qn_0}{\varepsilon} \left[ \exp\left(-\frac{q\psi(x)}{kT}\right) - \exp\left(\frac{q\psi(x)}{kT}\right) \right]$$

where  $\psi$  is the double layer potential,  $x$  is the direction normal to the interface,  $k$  is Boltzmann's constant and  $\varepsilon = 80\varepsilon_0$  is the dielectric constant of water. State all assumptions made. [20%]

(c) Assuming that the potential drop in the electrolyte is small compared to  $kT/q$ , where  $k$  is Boltzmann's constant, find the ratio  $\psi(x)/\psi(0)$  for  $x = 2 \times 10^{-9} \text{ m}$  and  $T = 300\text{K}$ . State all assumptions made. [30%]

(TURN OVER

3 (a) For the ferroelectric thin film material shown in Fig. 1, please estimate the:

(i) remnant polarisation; [10%]

(ii) coercive field; [10%]

(iii) energy density consumed in a full switching cycle. [10%]

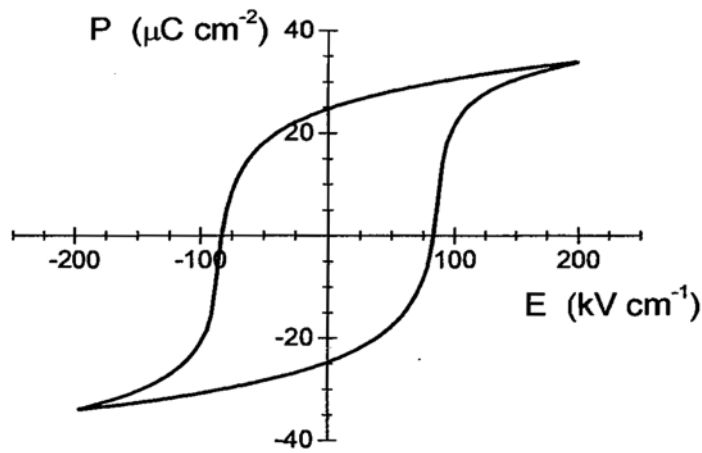


Fig. 1

(b) A ferroelectric thin film capacitor in a FRAM cell is made of the ferroelectric material shown in Fig. 1 with dimensions of 150 nm thickness and  $0.18\mu\text{m} \times 0.18\mu\text{m}$  square.

(i) If we apply a voltage across it in the form of a positive step function with a height of +3V, what will be the switching charges if the initial information stored in this memory cell was of State '1' (positively polarised) and State '0' (negative polarised), respectively? [15%]

(cont.)

(ii) If the bit line parasitic capacitance, which is utilised as a sensing capacitor, is 2pF, what are the sensed voltage levels for these two states, respectively? [15%]

(iii) Theoretically, how small can this capacitor be in order to maintain its original function as a memory cell, given that the Read-out sense amplifier has a resolution of 1mV? [20%]

(c) Figure 2 shows the results of an accelerated reliability test for the above memory cell. What are the projected life times of this device at 80°C and 30°C, respectively? (Hint: assume  $t_{\text{failure}} \sim \exp(+\Delta E/kT)$ , where  $\Delta E$  is a constant and  $k$  the Boltzmann constant.) [20%]

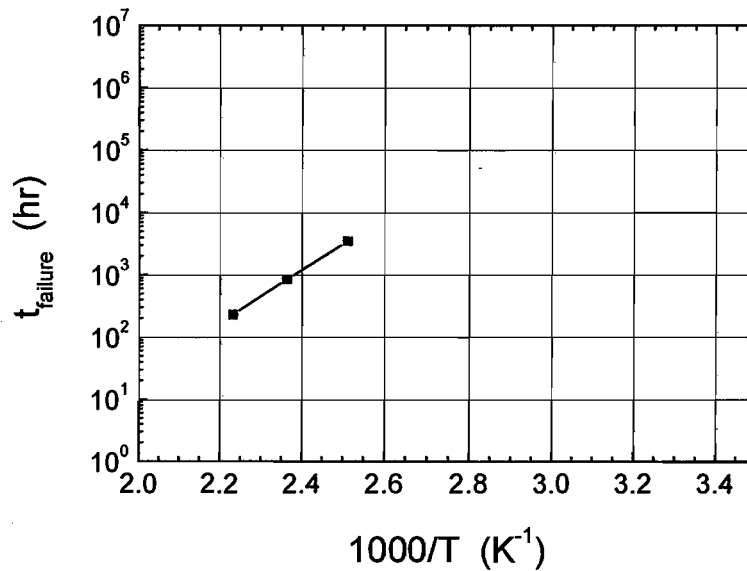


Fig. 2

(TURN OVER)

4 (a) A magnetic tunnel junction (MTJ) is operating in current-perpendicular-to-plane (CPP) configuration. It consists of two magnetic layers made of Co, which are separated by a thin non-magnetic layer made of Cu with a thickness of  $t_{Cu}$ , as shown in Fig. 3. The free energy of magnetic interaction,  $E$ , between the two Co layers can be described in the form of  $E = -J\vec{M}_{Co,1} \cdot \vec{M}_{Co,2}$ , where  $\vec{M}_{Co,1}$  and  $\vec{M}_{Co,2}$  are the in-plane magnetisations of the two Co layers, respectively, and  $J$  the exchange integral. Assume that the exchange integral is of RKKY-type interaction, i.e.  $J \sim \cos(2\pi\alpha t_{Cu})/(2\pi\alpha t_{Cu})^3$ , where  $\alpha$  is a constant. Sketch the exchange integral vs  $t_{Cu}$  and mark the regions of high and low magneto-resistance (HMR and LMR) when the external magnetic field is zero.

[50%]

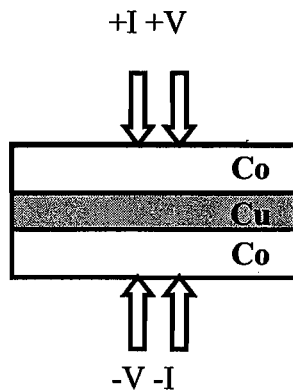


Fig. 3

(cont.)

- (b) The circuit representation of an MRAM cell is shown in Fig. 4. Use it to:
- draw a memory matrix linked by Bit-line, Word-line and Digit-line;
  - describe how to Read and Write a bit of information to and from a chosen cell, respectively.

[50%]

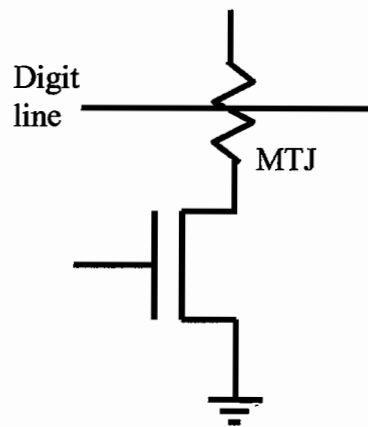


Fig. 4

**END OF PAPER**